

Patent Attorney's Docket No. <u>015290-238</u>

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re P	atent Application of	)			
Jeffrey	HUNG et al.	Group Art Unit: 1765			
Applic	ation No.: 09/002,007	) Examiner: L. Vinh			
Filed:	December 31, 1997	)			
For:	ETCHING PROCESS FOR ORGANIC ANTI-REFLECTIVE COATING	) ) ) )			
	AMENDMENT/REPLY T	RANSMITTAL LETTER			
	ant Commissioner for Patents ngton, D.C. 20231				
Sir:					
Eı	nclosed is a reply for the above-identified pa	tent application.			
[	] A Petition for Extension of Time is also	enclosed.			
[	A Terminal Disclaimer and a check for requisite Government fee are also enclo	[] \$55.00 (248) [] \$110.00 (148) to cover the sed.			
[	] Also enclosed is				
[	] Small entity status is hereby claimed.	ROOM			
[	Applicant(s) request continued examinate the [] \$355.00 (279) [] \$710.00 (179) fee	tion under 37 C.F.R. § 1.114 and enclose			
	[ ] Applicant(s) previously submitted requested.	, on, for which continued examination is			
[	A Request for Entry and Consideration (146/246) is also enclosed.	A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (146/246) is also enclosed.			
ſx	No additional claim fee is required				

[ ] An additional claim fee is required, and is calculated as shown below:

AMENDED CLAIMS						
	No. OF CLAIMS	HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	ADDT'L FEE	
Total Claims	20	MINUS 20 =	0	× \$18.00 (103) =	0.00	
Independent Claims	3	MINUS 3 =	0	× \$80.00 (102) =	0.00	
If Amendment adds mu	ıltiple depende	ent claims, add \$270	.00 (104)			
Total Amendment Fee	0.00					
If small entity status is						
TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT					0.00	

[	]	A claim fee in the	amount of \$	is enclosed.
[	]	Charge \$	to Deposit Account N	To. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R.

§§ 1.16, 1.17, 1.20(d) and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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Date: October 13, 2000



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ANTI-REFLECTIVE COATING	)

## **AMENDMENT**

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Official Action dated July 13, 2000, please amend the aboveidentified application as follows.

## **REMARKS**

Favorable reconsideration of this application in light of the following remarks is respectfully requested.

The present invention broadly relates to etching an organic anti-reflective coating (ARC). In particular, the present invention sets forth a process for removing exposed areas of an organic ARC on a metallic layer, the exposed areas of the ARC having been exposed by previously etching a photoresist covering the ARC. The process comprises exposing the exposed areas of the ARC to an oxygen-free system of etching agents in an ionized state in